

# **Perspectives from EB Mask Writer**



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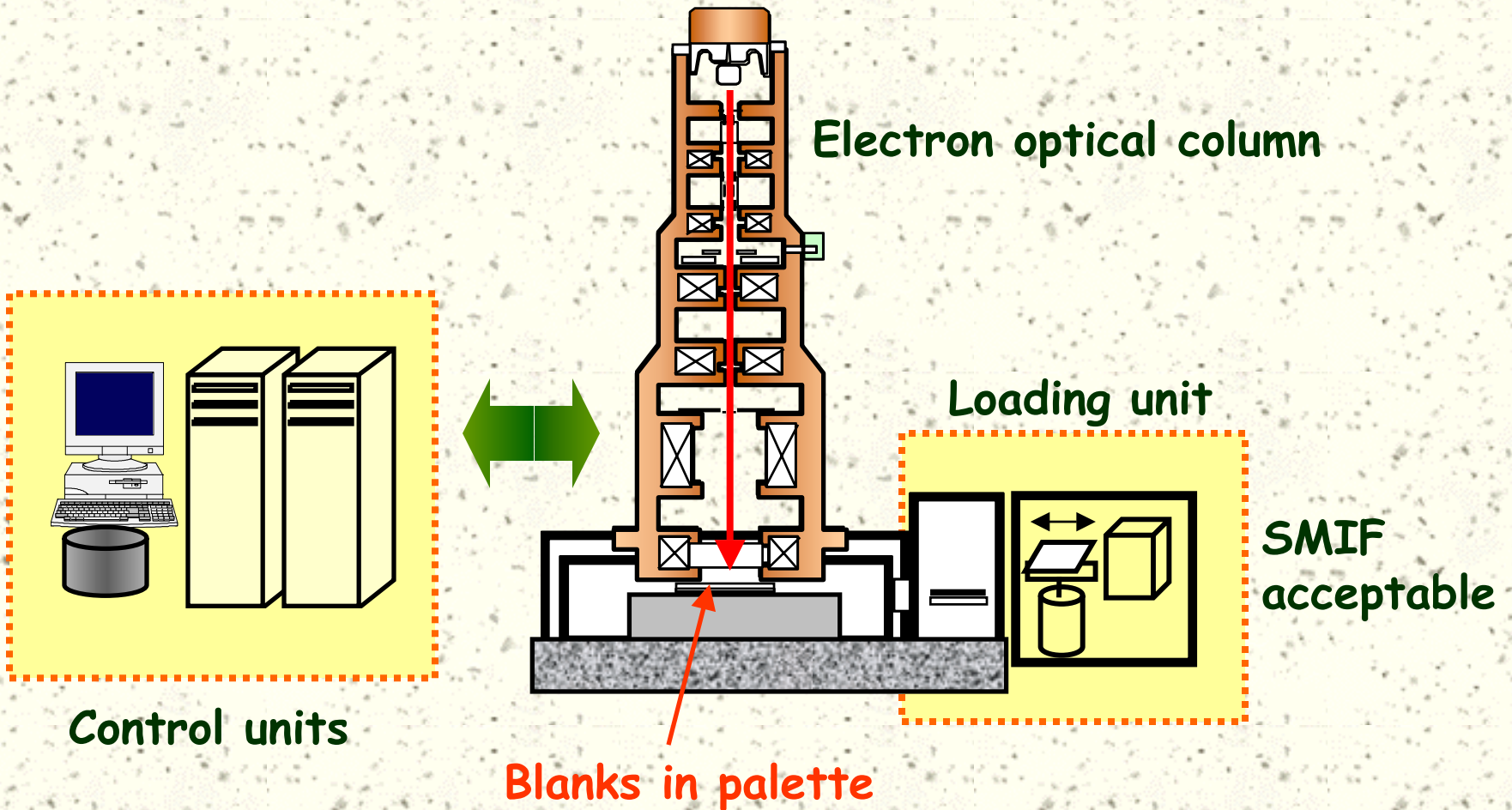
- Focused on the substrate handling -

- Current EB writer

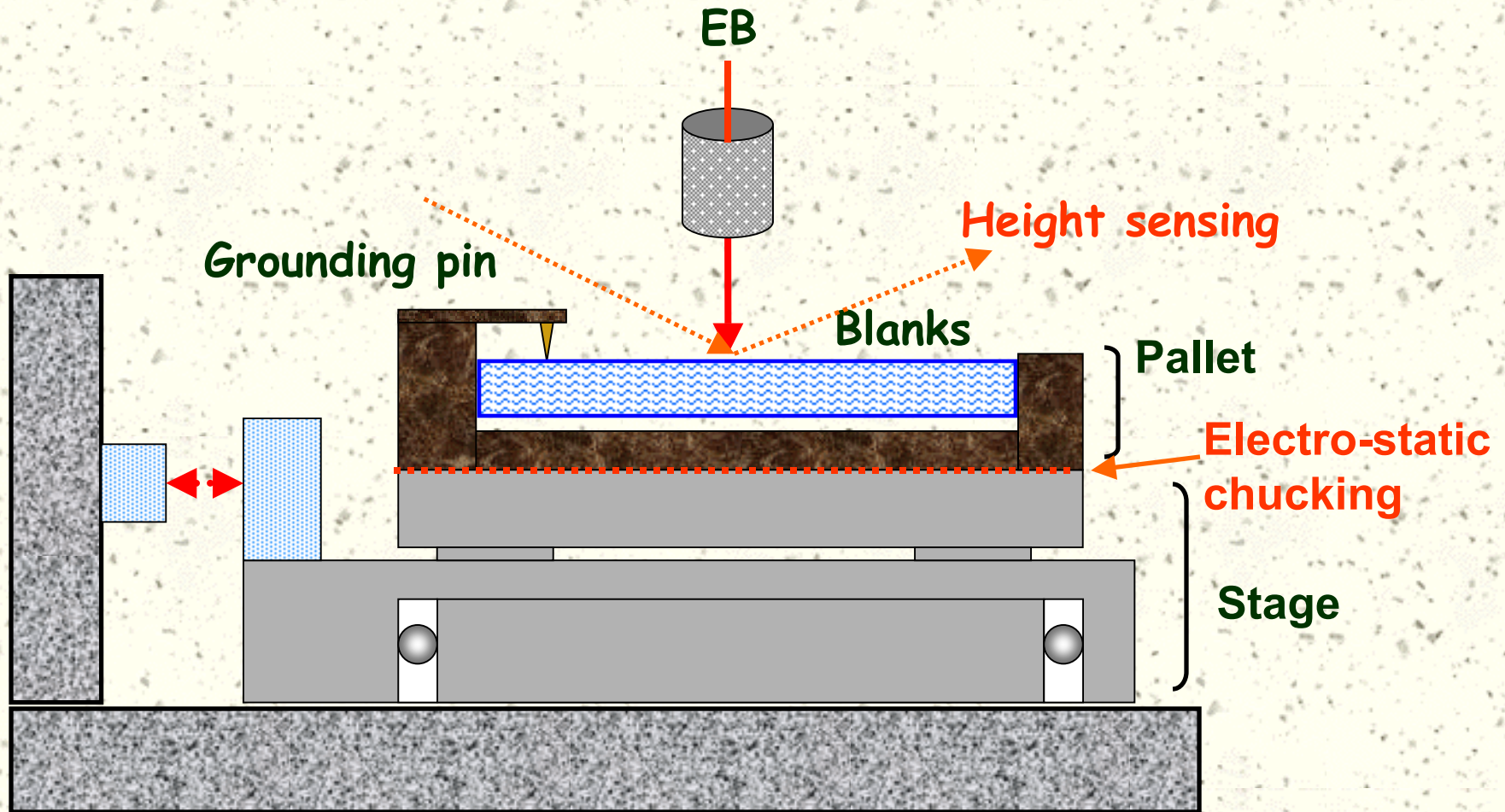
- General concerns

- Messages

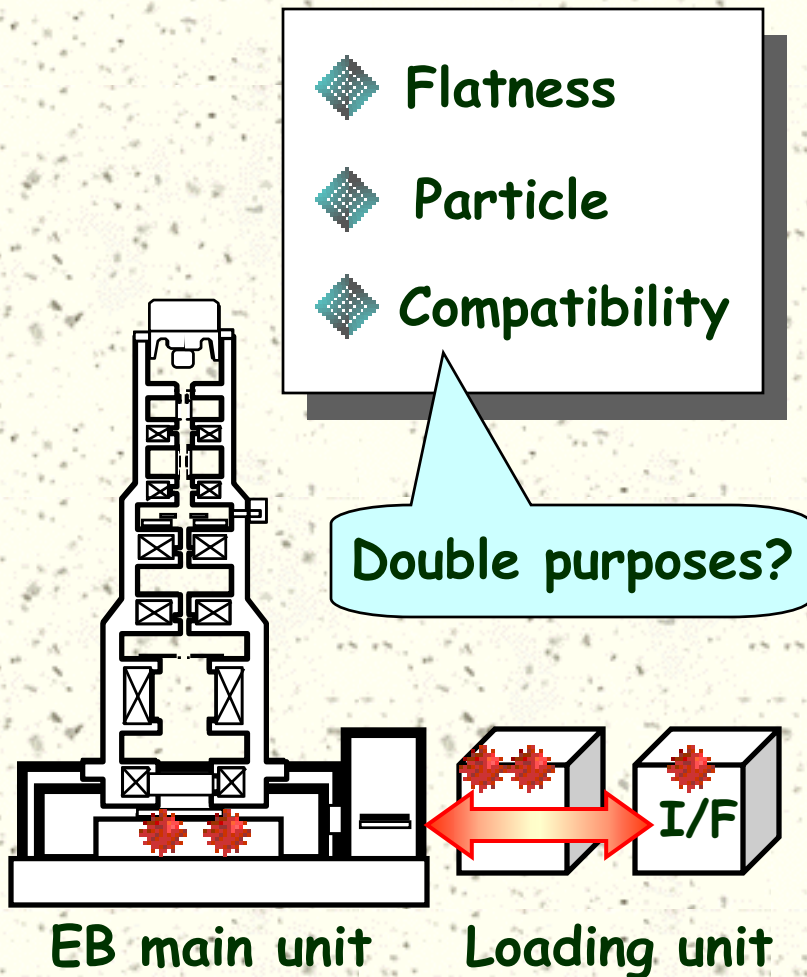
# EB writer



# Stage configuration - Cross section -



# General concerns



- ✱ Interface with carrier
- ✱ Handling method during transportation
- ✱ Pellicle handling (how to put on & take off, where)
- ✱ Height sensing (compensation)
- ✱ Cramping method during exposure

# Messages from a EB supplier

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- Flatness and particle control are major concerns when writer handles EUV mask.
- Standardization of EUV mask handling is desirable.
- Standards will be respected when the writer is designed.

*FIN*